

FIG. 1

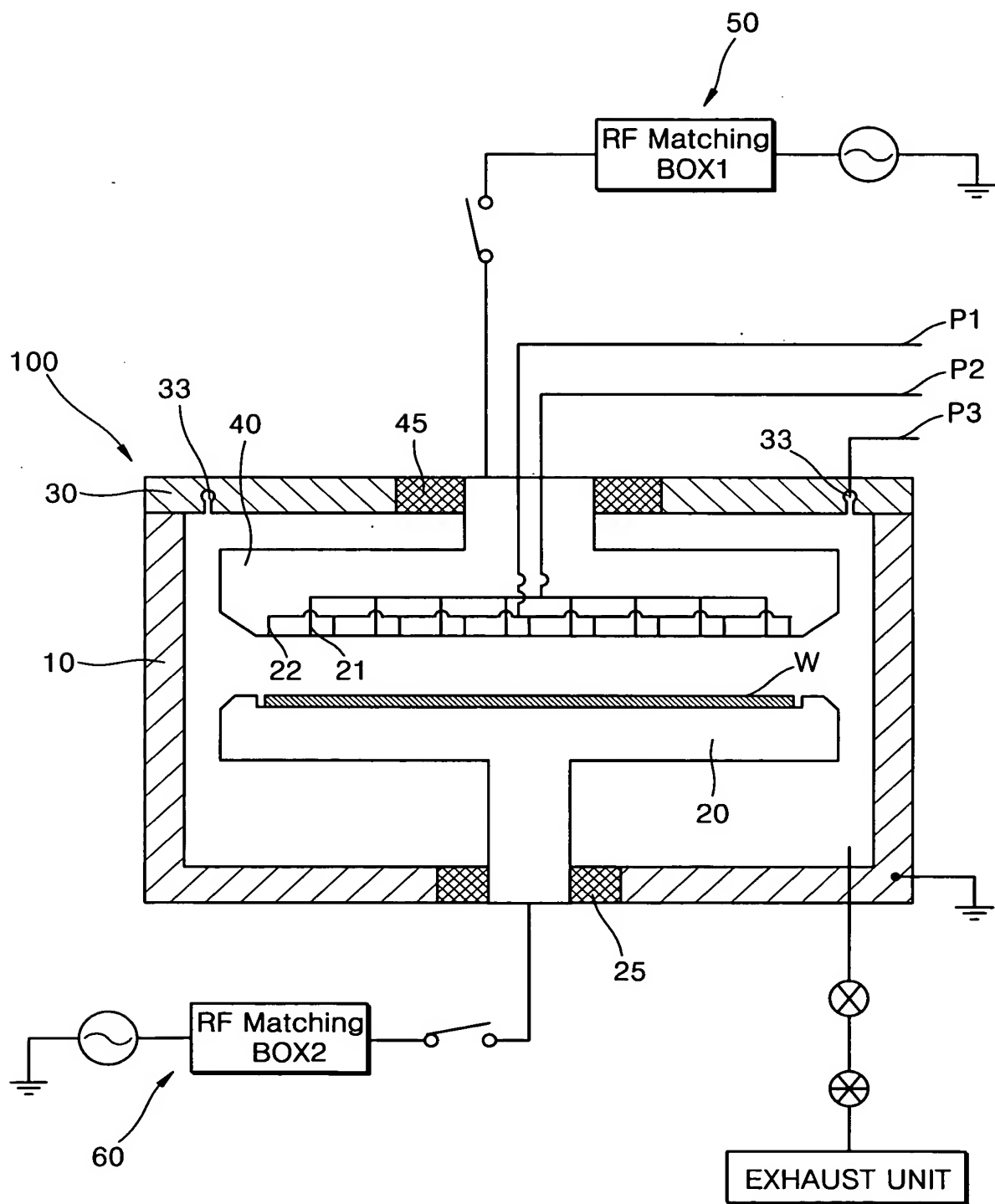


FIG. 2

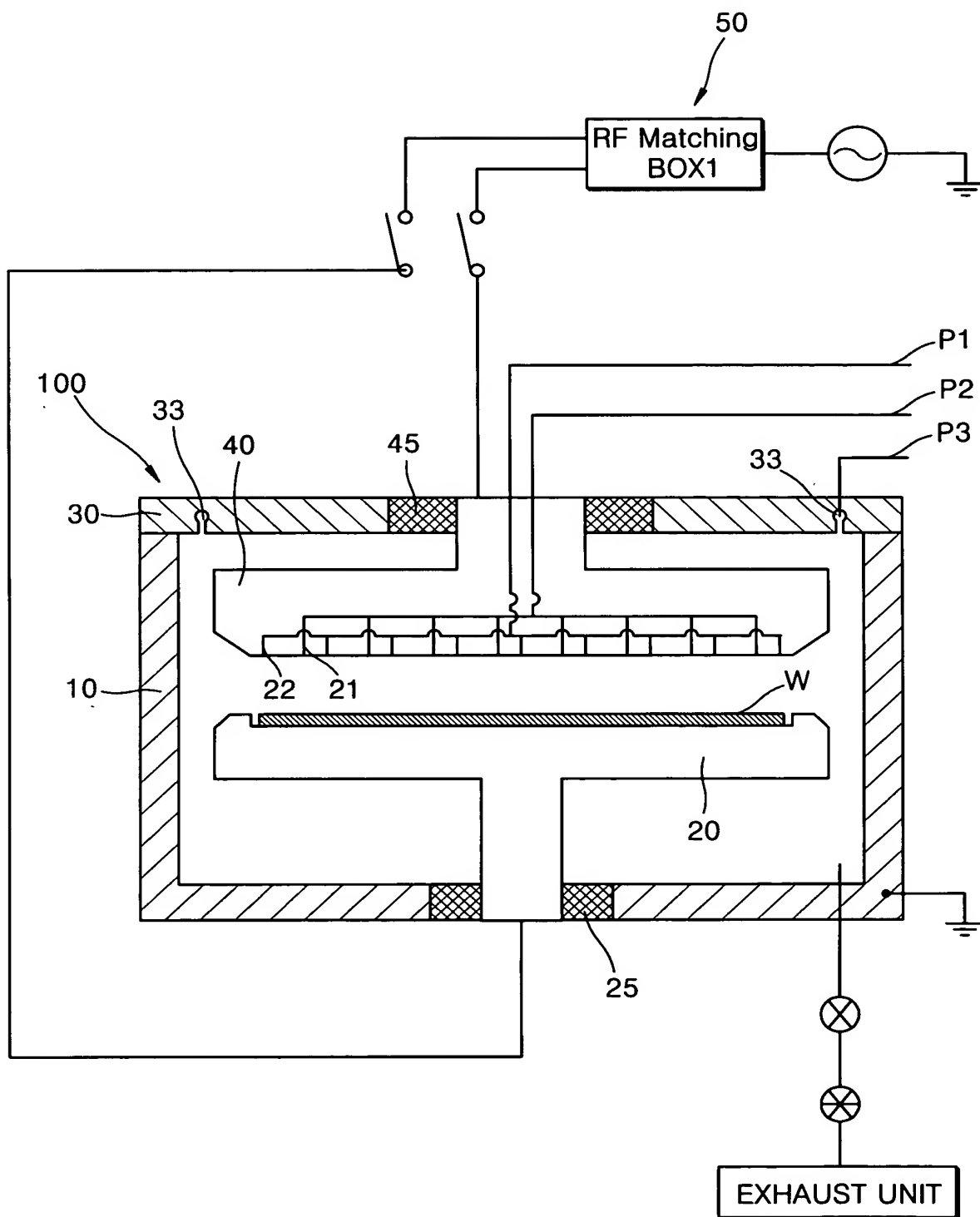
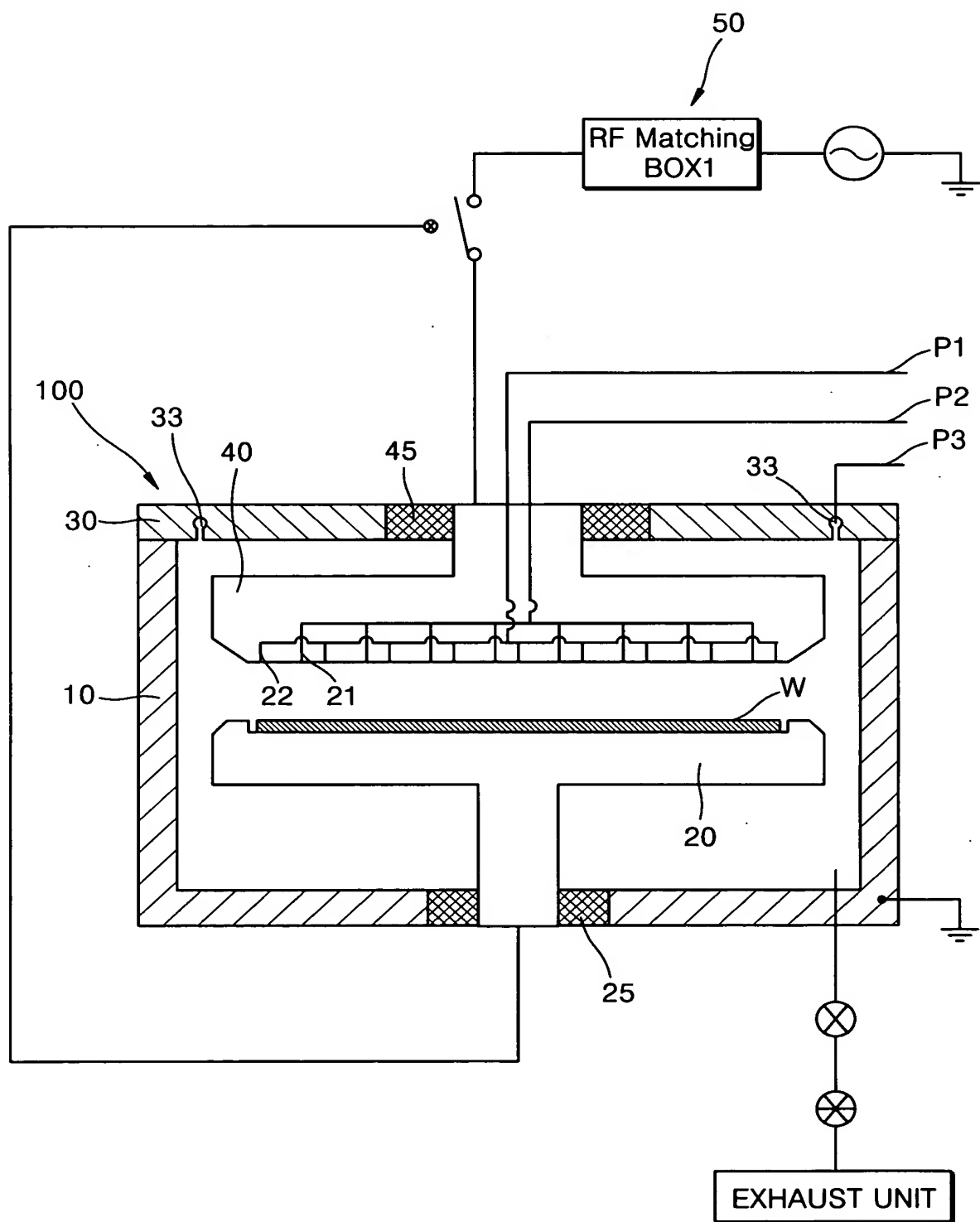


FIG. 3



# FIG. 4

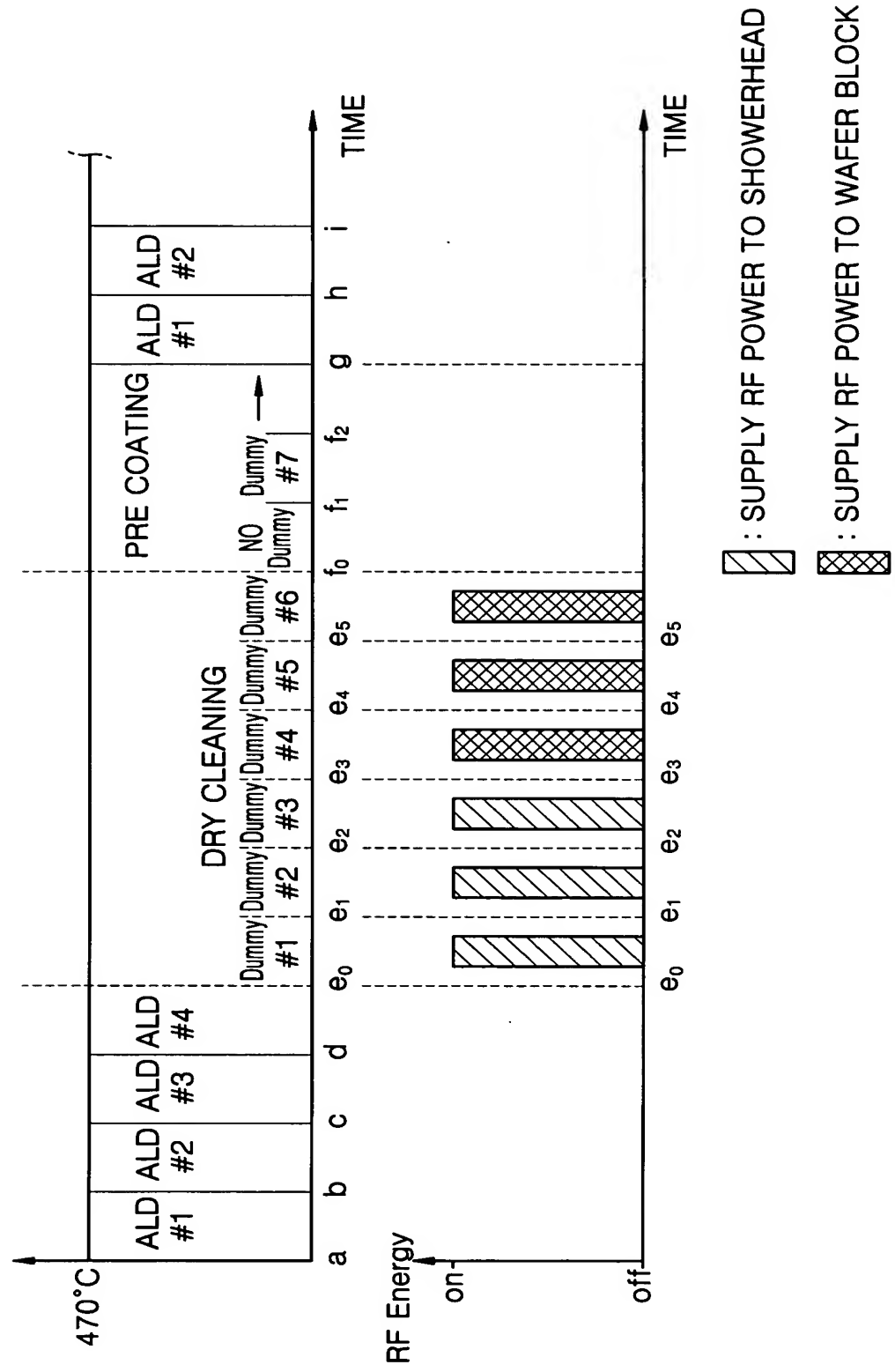


FIG. 5

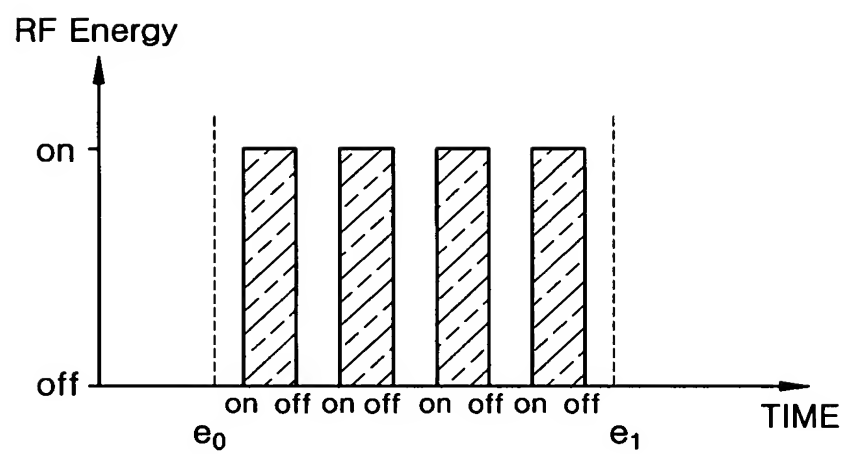


FIG. 6

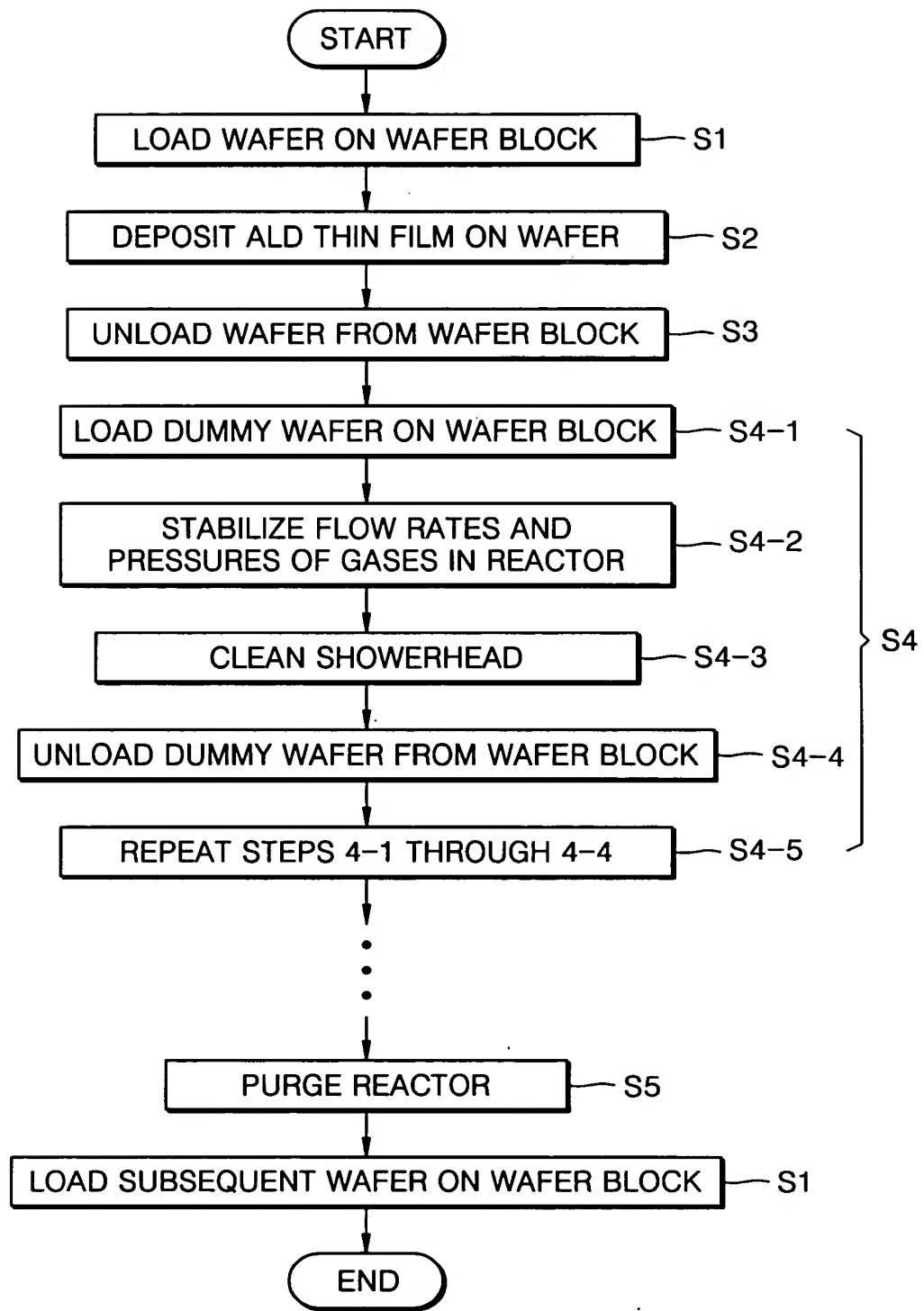


FIG. 7

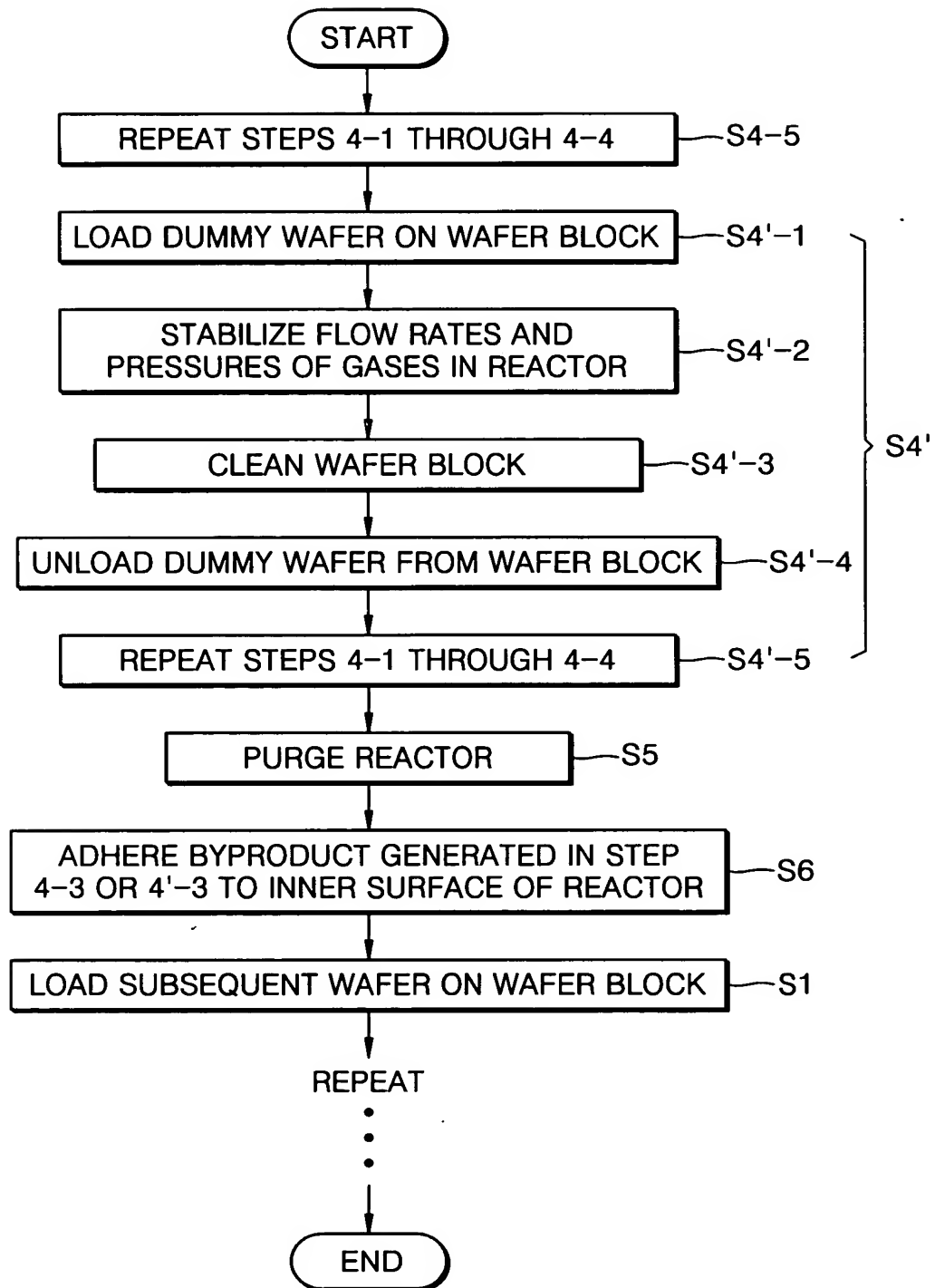


FIG. 8

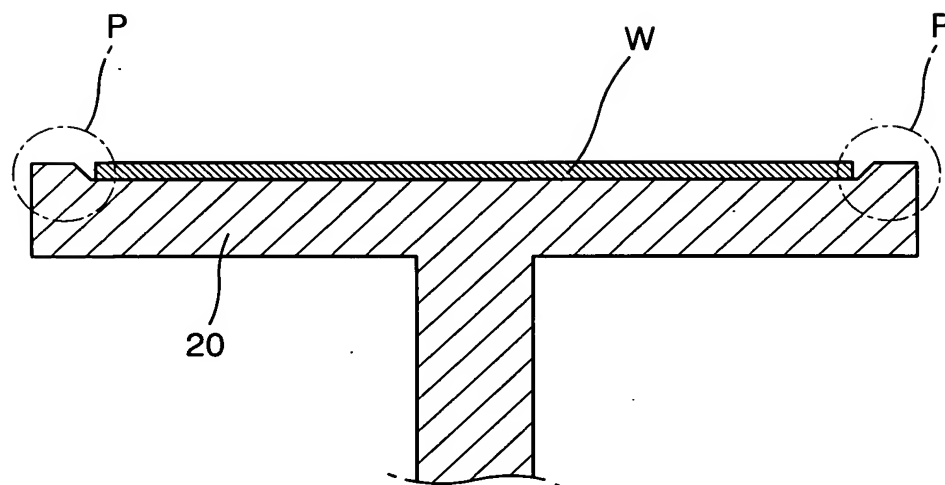


FIG. 9

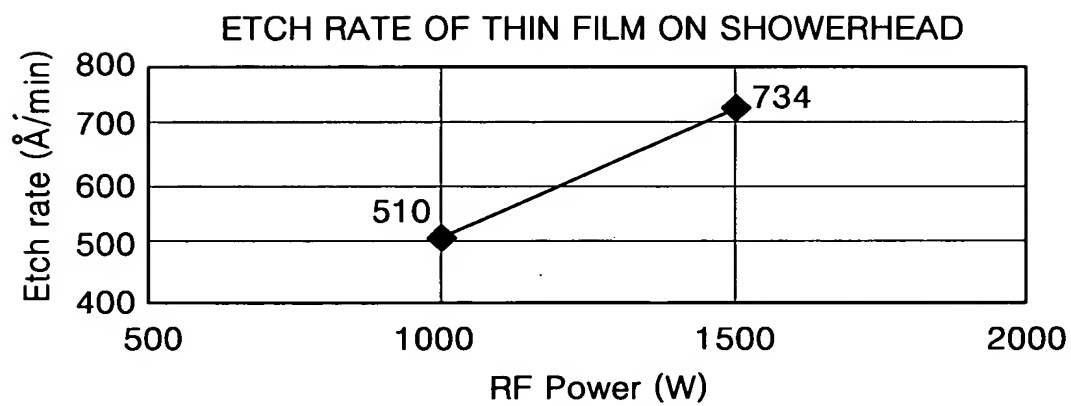




FIG. 10

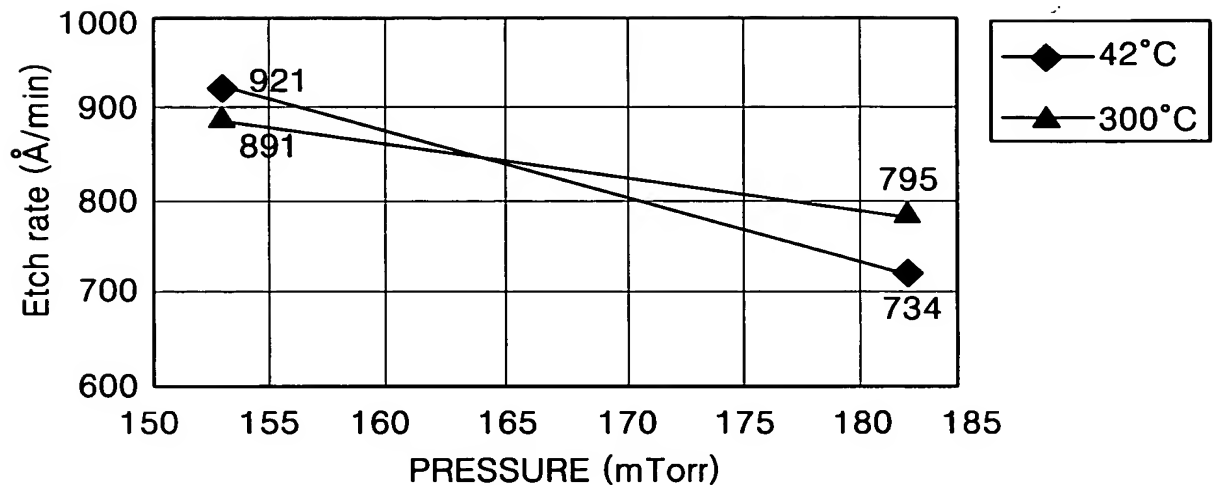


FIG. 11

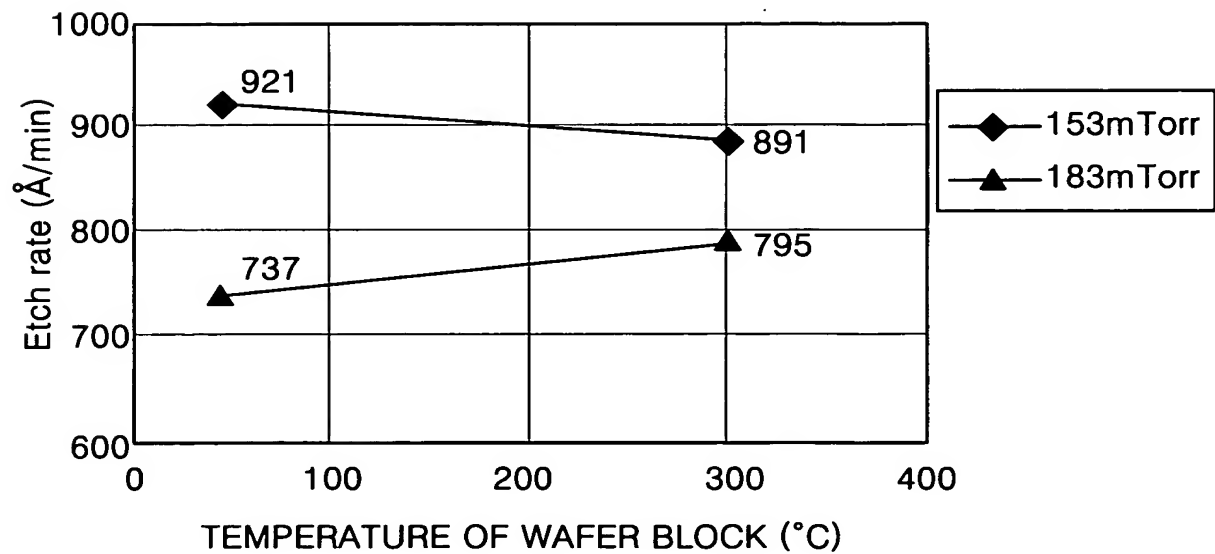


FIG. 12

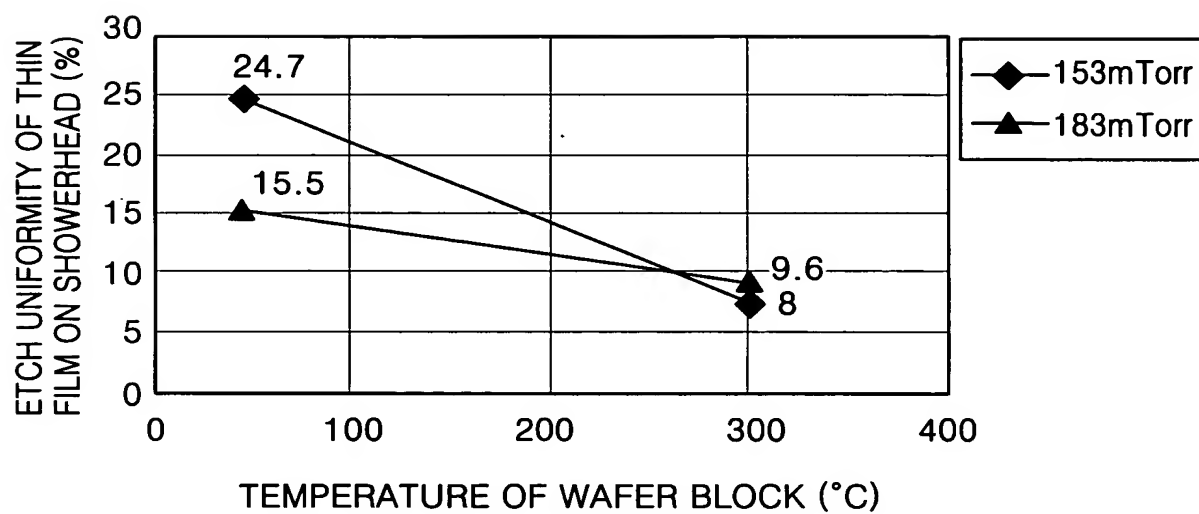
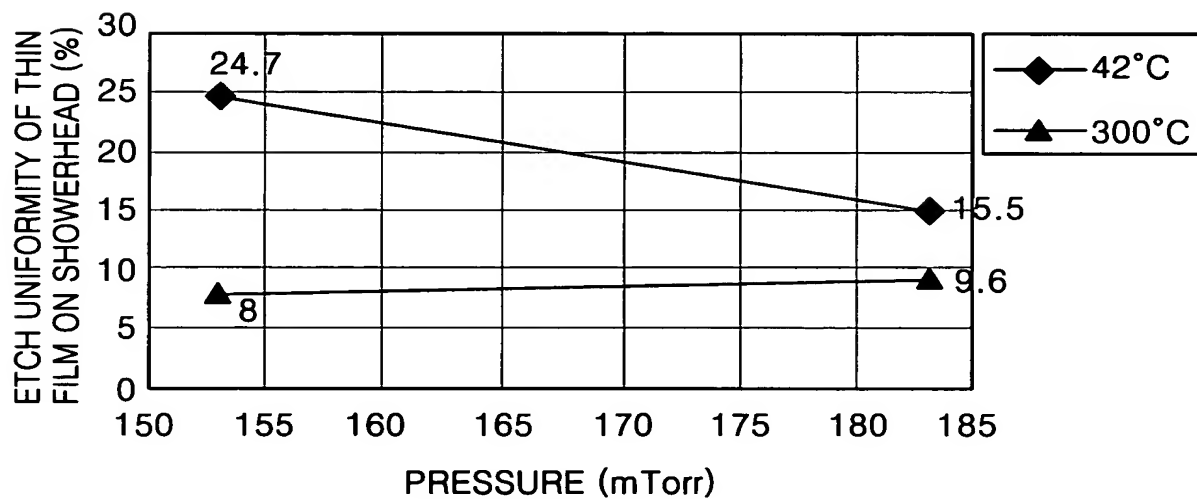


FIG. 13

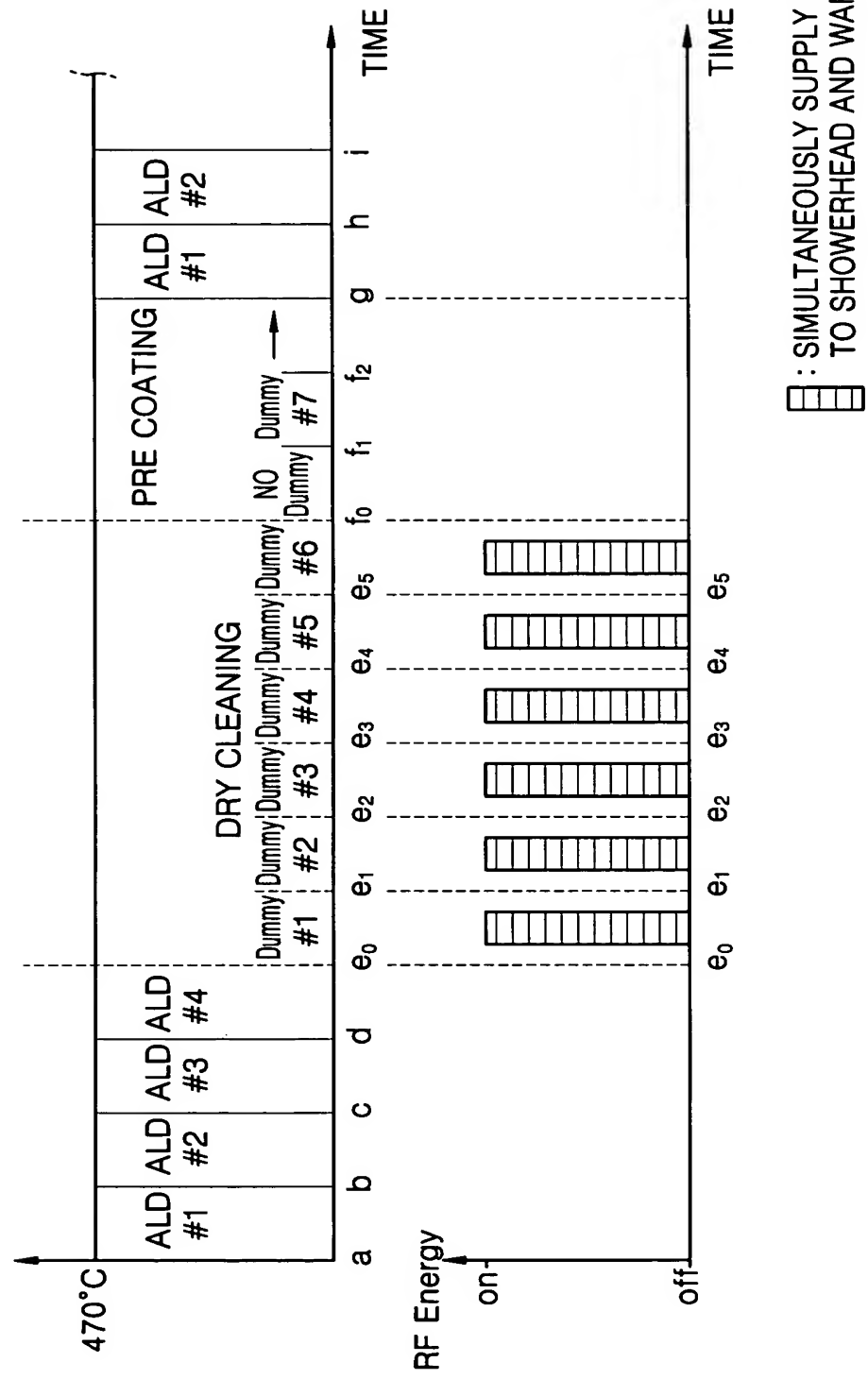


# FIG. 14

TEMPERATURE OF WAFER BLOCK (°C)/ PRESSURE (mTorr)	183	153
42	734Å/min ± 15.5%	921Å/min ± 24.7%
300	795Å/min ± 9.6%	891Å/min ± 8.0%

- a) UNDER 183mTorr : BCl<sub>3</sub>(70sccm), Ar(30sccm), 1.5KW  
b) UNDER 153mTorr : BCl<sub>3</sub>(50sccm), Ar(20sccm), 1.5KW

FIG. 15



# FIG. 16

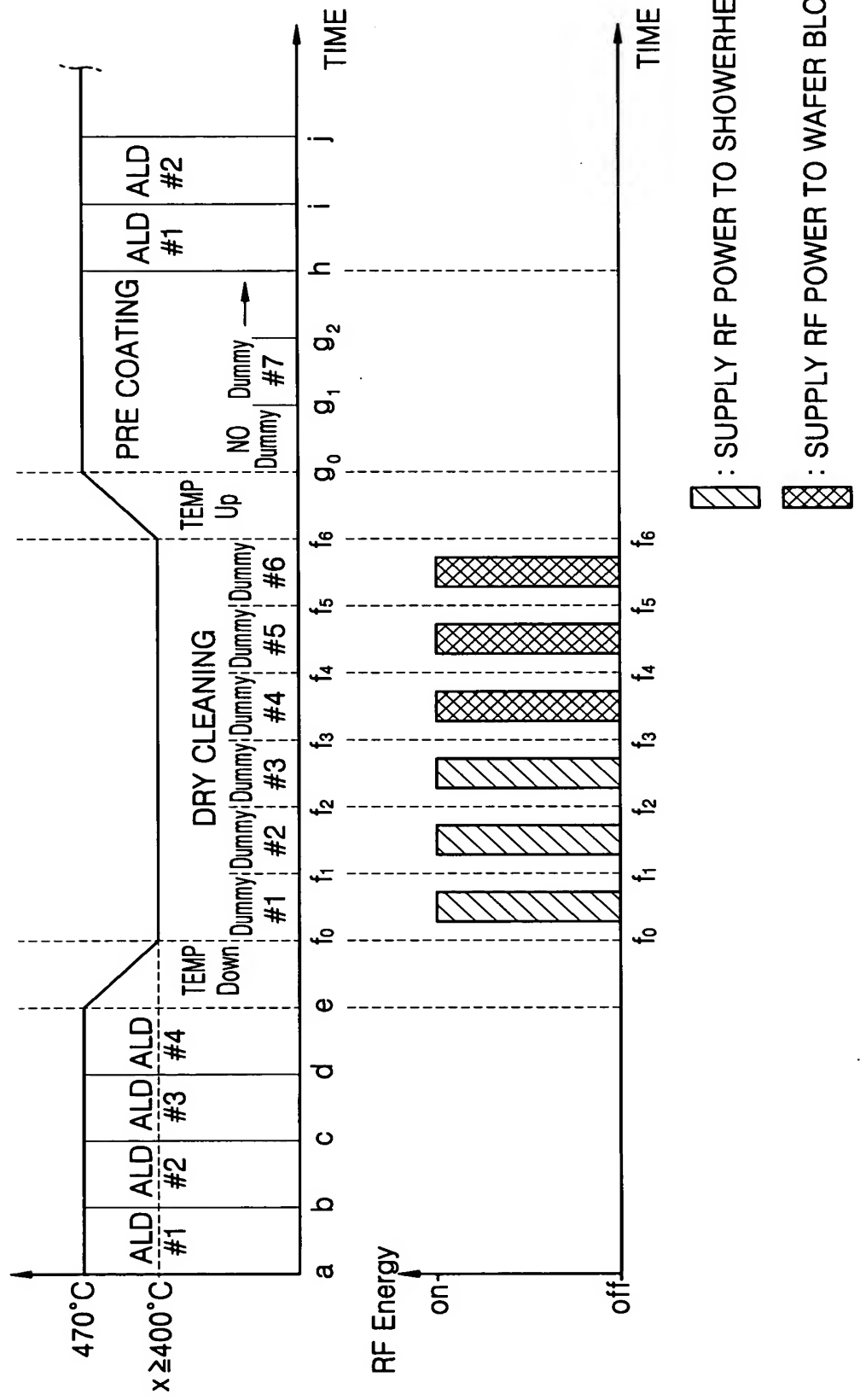
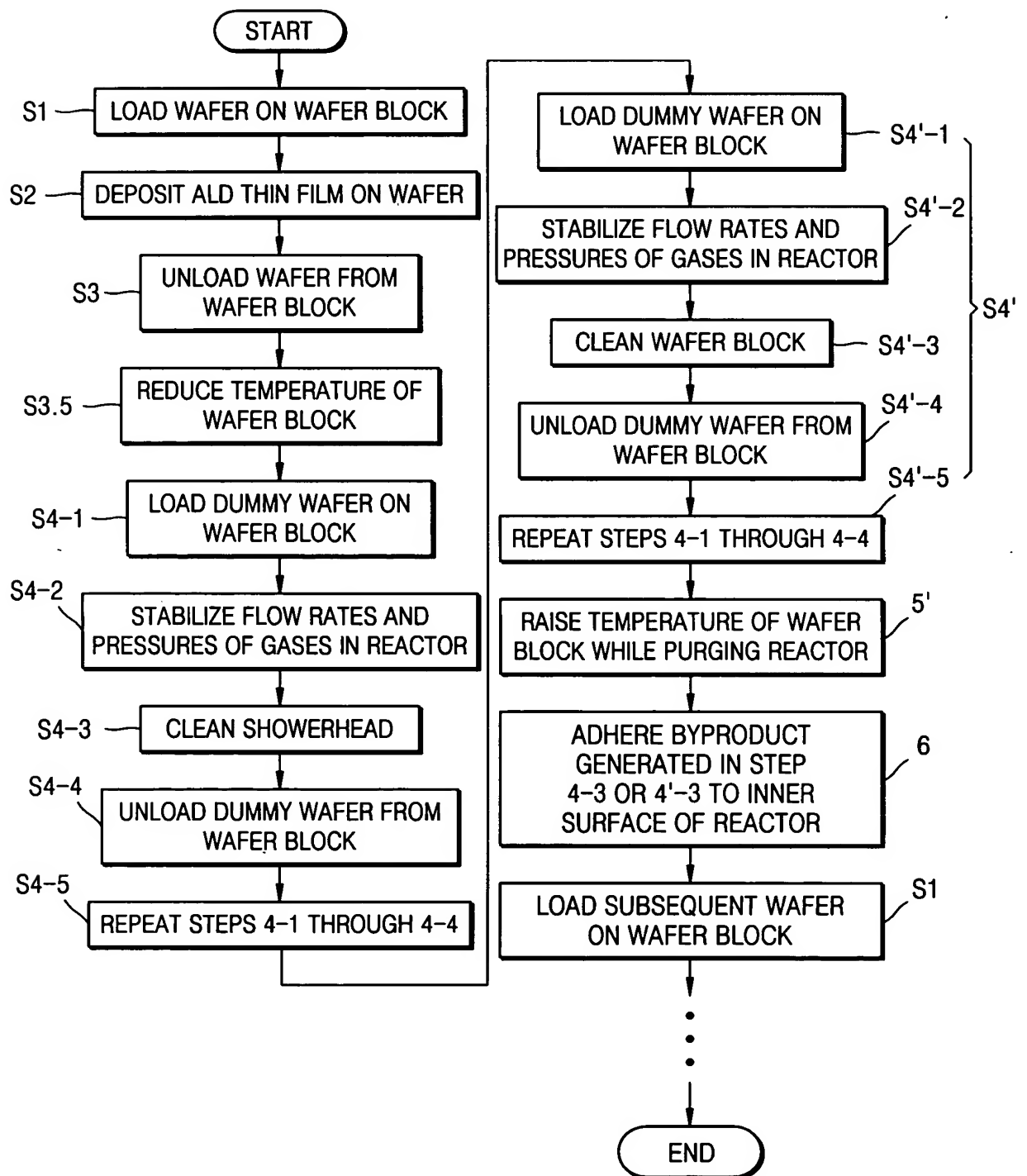


FIG. 17



# FIG. 18

